

DOCKET NO.: 0160-0193-0 PCT/hyc

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN RE APPLICATION OF: Hiroshi IKEDA, et al.

SERIAL NUMBER: 09/463,961

GROUP: 1754

FILED: March 9, 2000

EXAMINER: Wayne A. LANGE

FOR: PROCESS AND APPARATUS FOR TREATING SEMICONDUCTOR  
PRODUCTION EXHAUST GASES

**REQUEST TO CORRECT TITLE OF INVENTION**

MAIL STOP ISSUE FEE  
COMMISSIONER FOR PATENTS  
P.O. BOX 1450  
ALEXANDRIA, VA 22313-1450

SIR:

In the matter of the above-identified application for patent, we hereby request  
correction of your records to reflect the correct title of the invention. The title of the  
invention should read as follows: **PROCESS AND APPARATUS FOR TREATING  
SEMICONDUCTOR PRODUCTION EXHAUST GASES.**

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.  
Norman F. Oblon



Vincent K. Shier, Ph.D.  
Registration No. 50,552

Customer Number

**22850**

Tel. (703) 413-3000  
Fax. (703) 413-2220  
(OSMMN 05/04)

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Surinder Sachar  
Registration No. 34,423

Docket No.: 0160-0193-0 PCT/hyc



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EXAMINER: Wayne A. LANGEL

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PRODUCTION EXHAUST GASES

**REQUEST TO CORRECT FILING DATE**

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COMMISSIONER FOR PATENTS  
P.O. BOX 1450  
ALEXANDRIA, VA 22313-1450

SIR:

In the matter of the above-identified application, we hereby request correction of your records to reflect the correct filing date of the invention. The correct filing date of the invention should be: **March 9, 2000**, as evidenced by the copy of the date-stamped filing receipt.

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.  
Norman F. Oblon

Vincent K. Shier, Ph.D.  
Registration No. 50,552

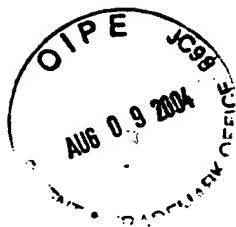
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Surinder Sachar  
Registration No. 34,423



O.S.&M. File No. 0160-0193-0 PCT B y NFO/dtv FF

Due Date NONE

Serial No. 09/463,961

In the Matter of the Application of Hiroshi IKEDA, et al.

For PROCESS AND APPARATUS FOR TREATING  
SEMICONDUCTOR PRODUCTION EXHAUST GASES

The following has been received in the U.S. Patent Office on the date stamped hereon:

- ☐      pps. Specification &      Claims (English Translation)
- ☒ Combined Declaration, Petition & Power of Attorney (3 pages)
- ☒ Submission of Declaration under 37 CFR 1.495
- ☒ PCT Transmittal Letter
- ☐ Verified Statement (Declaration) Claiming Small Entity Status
- ☐ Submission of Verified Statement (Declaration) Claiming Small Entity Status
- ☐ Check for \$                     ; ☒ Dep. Acct. Order Form
- ☐ Declaration of
- ☐ Assignment            pages/PTO-1595
- ☐ Letter to Official Draftsman
- ☐ Letter Requesting Approval of Drawing Changes
- ☐ Drawings      sheets
- ☒ Preliminary Amendment
- ☐ Information Disclosure Statement; ☐ PTO-1449
- ☐ Cited References (      )
- ☐                      Search Report
- ☐ Statement of Relevancy
- ☐ Restriction Response ☐ Election Response
- ☐ Rule 132 Declaration
- ☐ Petition
- ☐ Notice of Appeal

**95 Rec'd PCT/PTO 09 MAR 2000**  
Date Rec'd